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MATERIAL FOR FORMING RESIST-PROTECTING FILM FOR IMMERSION EXPOSURE PROCESS, RESIST-PROTECTING FILM MADE OF THE PROTECTING FILM FORMING MATERIAL, AND METHOD FOR FORMING RESIST PATTERN USING THE RESIST-PROTECTING FILM

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Abstract of JP 2005099648 (A)

PROBLEM TO BE SOLVED: To provide a material for forming a resist-protecting film for immersion exposure process which is preferably used in an immersion exposure process wherein there is used a nonaqueous liquid with high transparency and high refractive index as typified by fluorine-containing liquids. ; SOLUTION: The material for forming a resist-protecting film for immersion exposure process contains at least one component selected from water-soluble and alkali-soluble film-forming materials. The immersion exposure process is characterized in that the resolution of the resist pattern is improved by exposing a resist film to light via the nonaqueous liquid of a certain thickness which has a refractive index higher than that of the air and is disposed at least on the resist film within the path where a lithography exposure light propagates through to the resist film. ; COPYRIGHT: (C)2005,JPO&NCIP

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